

**METHOD OF MAKING NiFeCo-O-N OR NiFeCo-N FILMS
FOR SHIELDS AND/OR POLES OF A MAGNETIC HEAD**

ABSTRACT OF THE DISCLOSURE

5 A specified amount of N₂O or N₂ is employed in a process gas of a DC magnetron for sputter depositing single or laminated films of NiFeCo-O-N or NiFeCo-N with a high uniaxial anisotropy H_K after annealing these films along their hard axes. The films can be used for shield layers and/or pole piece layers in a magnetic head.

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